

# Transition-Metal-Catalyzed Silylene Expulsion from, and/or Rearrangement of, Oligosilanes

Keith H. Pannell,\* Mari-Carmen Brun, Hemant Sharma, Karen Jones, and Sneh Sharma

Department of Chemistry, University of Texas at El Paso, El Paso, Texas 79968-0513

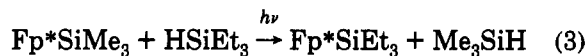
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**Summary:** Photochemical treatment of  $\text{HSiMe}_2\text{SiMe}_2\text{R}$  ( $\text{R} = \text{Me}$ ) with a catalytic amount of  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})_2\text{-SiMe}_3$  (**1**) led to the high-yield formation of  $\text{Me}_2\text{Si}$ , trapped efficiently with  $\text{HSi}(\text{SiMe}_3)_3$ . The use of  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})(\text{PPh}_3)\text{SiMe}_3$  (**2**) as catalyst in a thermal reaction does not produce silylene but causes isomerization of the disilane ( $\text{R} = \text{Ph}$ ). Photochemical treatment of  $\text{HSiMe}_2\text{SiMe}_2\text{SiMe}_2\text{SiMe}_3$  with a catalytic amount of **1** initially produced  $\text{HSi}(\text{SiMe}_3)_3$  with further transformation to  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  via silylene insertion. However, thermal catalysis using **2** yielded only  $\text{HSi}(\text{SiMe}_3)_3$ . Both thermal and photochemical catalytic processes proceed via equilibrating Fe silyl silylene intermediates.

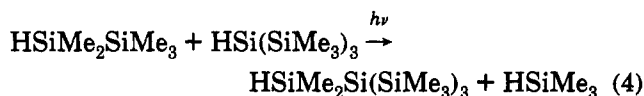
The photochemical transformation of disilyl and trisilyl derivatives of  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})_2$  (Fp), resulting in the elimination of  $\text{SiR}_2$ , is well-established (eq 1).<sup>1-3</sup> In contrast, linear and cyclic oligosilyl groups containing four or more Si atoms result predominantly in high-yield isomerization reactions to form tris(silyl)silane derivatives (eq 2).



These reactions proceed via equilibrating silyl silylene complexes, i.e.,  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})(=\text{SiMe}_2)\text{Si}_n\text{Me}_{2n+1}$ , formed by  $\alpha$ -elimination subsequent to initial CO expulsion. In the case of the disilane ( $n = 1$ ) the silylene is readily eliminated, whereas for the tetrasilane, and higher homologs, a series of 1,3-silyl and -methyl migrations proceed down a thermodynamic chain, resulting in the photostable tris(silyl)silane product. The desirability of performing such transformations of oligosilanes in a catalytic manner is self-evident. Randolph and Wrighton have reported that silyl exchange is readily effected upon photochemical irradiation of  $\text{Fp}^*\text{SiMe}_3$  and  $\text{Et}_3\text{SiH}$ , a reaction that proceeds via initial CO loss, oxidative addition of  $\text{Et}_3\text{SiH}$  to the resulting 16-electron intermediate, reductive elimination of  $\text{Me}_3\text{SiH}$ , and recoordination of CO (eq 3).<sup>2,4</sup>



We report that a combination of the above reactions may be used to perform the silylene generation from disilanes (eq 1) and oligosilane isomerization (eq 2) in a catalytic manner using the intermediate  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})\text{-SiMe}_3$  generated photochemically from  $\text{FpSiMe}_3$  (**1**) or thermally from  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})(\text{PPh}_3)\text{SiMe}_3$  (**2**).<sup>5</sup> In a typical silylene generation reaction photochemical treatment of  $\text{HSiMe}_2\text{SiMe}_3$  in the presence of 5% **1** in a sealed Pyrex NMR tube led to the total transformation of the disilane to  $\text{HSiMe}_3$  and  $\text{SiMe}_2$ . The silylene was trapped by either 2,3-dimethylbutadiene (27% yield) or  $\text{HSi}(\text{SiMe}_3)_3$  (78%) (eq 4).<sup>6a</sup> The catalytic cycle is detailed in



Scheme 1 (cycle A), and the results are closely related to the pioneering studies by the Kumada group involving silylene generation from  $\text{HSiMe}_2\text{SiMe}_3$  catalyzed by platinum and nickel complexes.<sup>7</sup>

Similar photochemical treatment of mixtures of  $\text{HSiMe}_2\text{-SiMe}_3$  with either of the trapping agents used above, in Pyrex tubes but without **1**, failed to produce any chemistry.

(4) Randolph, C. L.; Wrighton, M. S. *J. Am. Chem. Soc.* **1986**, *108*, 3366.

(5) King, R. B.; Pannell, K. H. *Inorg. Chem.* **1968**, *7*, 1510.

(6) (a) A 5-mm Pyrex NMR tube was charged with 0.1 g (0.76 mmol) of  $\text{HSiMe}_2\text{SiMe}_3$ , 0.1 g (0.40 mmol) of  $\text{HSi}(\text{SiMe}_3)_3$ , and 5 mol % of **1** in 1.5 mL of dry benzene and sealed under vacuum. Photolysis using a Hanovia 450-W lamp at a distance of 10 cm was monitored by <sup>29</sup>Si NMR spectroscopy. After 10 h the  $\text{HSiMe}_2\text{SiMe}_3$  had been consumed and resonances associated with the insertion product  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  were observed (-9.15, -33.0, and -136.4 ppm) together with a minor amount of  $\text{HSiMe}_2\text{SiMe}_2\text{Si}(\text{SiMe}_3)_3$  (-9.17, -15.7, -39.9, -132.2 ppm). GC/MS indicated the formation of the two products in 89% and 11% yields, respectively. The NMR solution was diluted into 10 mL of hexane and passed through a small column (1 × 2 cm) of silica gel and the resulting solution evaporated to dryness. The solid white residue was recrystallized from hexane to yield pure  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  (0.096 g, 78%), whose spectroscopic and physical properties were identical with those reported.<sup>8</sup>

(b) In a manner identical with that above 0.2 g (0.81 mmol) of  $\text{HSiMe}_2\text{-SiMe}_3\text{SiMe}_2\text{SiMe}_3$  was irradiated for 13 h with <sup>29</sup>Si NMR monitoring. The disappearance of the starting material was noted along with the appearance of  $\text{HSi}(\text{SiMe}_3)_3$  and also  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$ . Resonances indicating the formation of small amounts of other silane species were also apparent. Upon completion of the reaction GC/MS analysis showed the presence of  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  (67%),  $\text{HSi}(\text{SiMe}_3)_3$  (6%),  $\text{HSiMe}_2\text{-SiMe}_2\text{Si}(\text{SiMe}_3)_3$  (6%), and small amounts of  $\text{HSi}_3\text{Me}_7$ , ferrocene, and  $\text{FpSi}(\text{SiMe}_3)_3$ . Chromatography of the mixture via a silica gel column (2 × 10 cm) yielded a white solid that was 87% and 13%, respectively,  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  and  $\text{HSiMe}_2\text{SiMe}_2\text{Si}(\text{SiMe}_3)_3$  (0.14 g). (c) A 5-mm Pyrex NMR tube was charged with 0.11 g (0.44 mmol) of  $\text{HSiMe}_2\text{-SiMe}_2\text{SiMe}_3$  and 5 mol % **2**. The tube was sealed under vacuum and placed in an oven maintained at 120 °C. The progress of the reaction was monitored by <sup>29</sup>Si NMR, and after 24 h no starting material was present, having been converted to  $\text{HSi}(\text{SiMe}_3)_3$  with trace amounts of  $\text{HSiMe}_2\text{-SiMe}_2\text{Si}(\text{SiMe}_3)_3$ . Workup as described above resulted in the isolation of 0.097 g (88%) of  $\text{HSi}(\text{SiMe}_3)_3$ .

(7) (a) Yamamoto, K.; Okinoshima, H.; Kumada, M. *J. Organomet. Chem.* **1971**, *27*, C31. (b) Yamamoto, K.; Okinoshima, H.; Kumada, M. *J. Am. Chem. Soc.* **1972**, *94*, 9263.

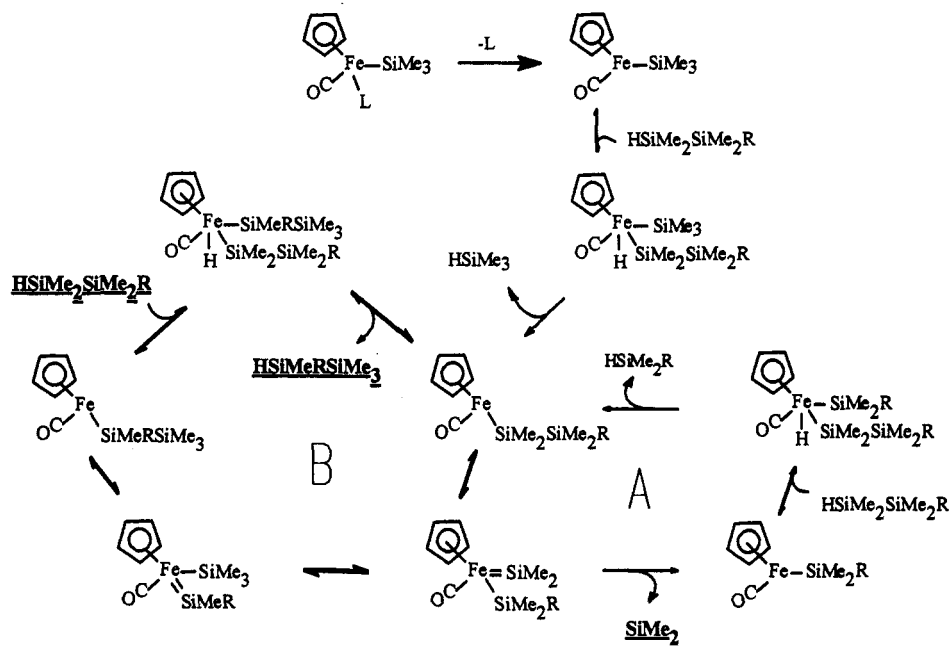
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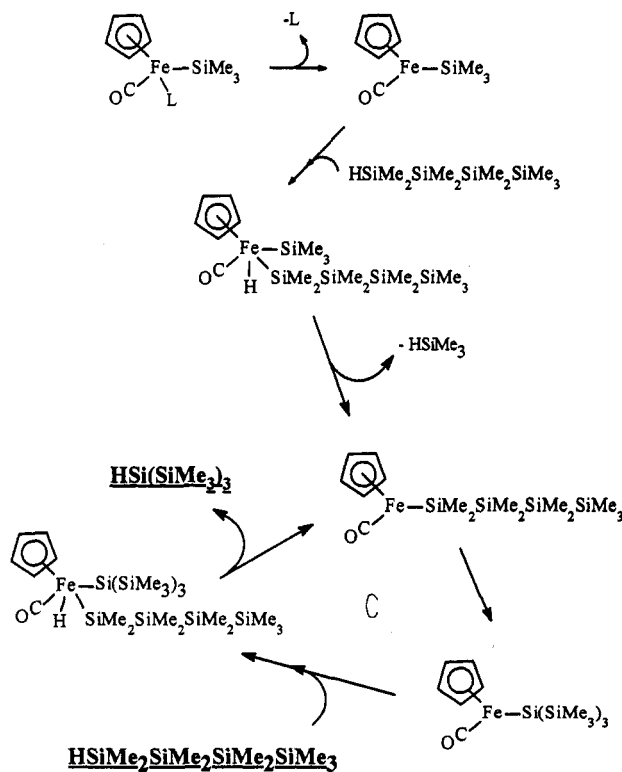
**Scheme 1. Catalytic Process for Silylene Generation: Photochemical with Catalyst 1 (Cycle A; R = Me) and Thermal Isomerization with Catalyst 2 (Cycle B; R = Ph)**

The Turner group has shown that the CO substitution of the silylene from  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})(=\text{SiMe}_2)\text{SiMe}_3$  to form  $\text{FpSiMe}_3$  is a photochemical event.<sup>3</sup> Since the thermal process does not cause silylene expulsion, thermal treatment of  $\text{HSiMe}_2\text{SiMe}_3$  and **2** in the presence of either 2,3-dimethylbutadiene or  $\text{HSi}(\text{SiMe}_3)_3$  resulted in no chemical transformations. To prove that thermally generated equilibrating silyl silylene complexes occurred in the case of disilanes, we treated both isomers  $\text{PhSiMe}_2\text{SiMe}_2\text{H}$  (**3**) and  $\text{HPhMeSiSiMe}_3$  (**4**) independently to the same thermal conditions described in the presence of catalyst **2**. Both reactions resulted in the formation of a mixture of **3** and **4** in the ratio 65:35, respectively, proving the thermal formation of equilibrating iron silyl silylene complexes (Scheme 1, cycle B).

To effect the isomerization of  $\text{HSiMe}_2\text{SiMe}_2\text{SiMe}_2\text{SiMe}_3$ , irradiation with  $\text{FpSiMe}_3$  (5%) was performed and led to rapid formation of  $\text{HSi}(\text{SiMe}_3)_3$ , and the catalytic scheme is shown in Scheme 2.<sup>6b</sup> However, further transformation to the dimethylsilylene insertion reaction product  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$  was observed and it is apparent that some silylene expulsion occurred from the linear  $(\eta^5\text{-C}_5\text{H}_5)\text{Fe}(\text{CO})\text{SiMe}_2\text{SiMe}_2\text{SiMe}_2\text{SiMe}_3$  intermediates, a result that we had not previously observed when following the high-yield reaction described in eq 2 via <sup>29</sup>Si NMR.

To retard the silylene elimination and subsequent formation of  $\text{HSiMe}_2\text{Si}(\text{SiMe}_3)_3$ , we used the thermal route with catalyst **2**. Treatment of a toluene solution of  $\text{HSiMe}_2\text{SiMe}_2\text{SiMe}_2\text{SiMe}_3$  with **2** (5%) in a sealed NMR tube at 120 °C resulted in the quantitative formation of  $\text{HSi}(\text{SiMe}_3)_3$  as the only observed product after 24 h (88% isolated yield).<sup>6c</sup>

Overall we have demonstrated that the chemistry of the Fp-oligosilane systems can be utilized to perform (a) catalytic silylene generation from disilanes (photochemically with catalyst **1**), (b) isomerization of disilanes (thermally with catalyst **2**), and (c) isomerization of linear oligosilanes using either method, but preferably the thermal route using **2** as catalyst. It is noteworthy that Blinka and West have shown that cyclosilanes may be

**Scheme 2. Catalytic Process for Oligosilane Isomerization: Photochemical with Catalyst 1 and Thermal with Catalyst 2**

isomerized by  $\text{AlCl}_3$  only if 1%  $\text{FeCl}_3$  is present;<sup>9</sup> however, we have also performed the photochemical isomerization of  $\text{HSiMe}_2\text{SiMe}_2\text{SiMe}_2\text{SiMe}_3$  using either  $\text{Fe}(\text{CO})_5$  or  $\text{W}(\text{CO})_6$  as catalyst and the thermal isomerization using  $(\eta^5\text{-C}_5\text{H}_5)\text{Ru}(\text{PPh}_3)_2\text{CH}_3$  as catalyst. The photochemical reactions proceed smoothly, however, as with the photochemical catalysts using **1**, subsequent to isomerization, some silylene insertion occurred. Using the Ru catalyst,

(9) Blinka, T. A.; West, R. *Organometallics* 1986, 5, 128.

a mixture of  $(\text{Me}_3\text{Si})_3\text{SiH}$  and  $(\text{Me}_3\text{Si})_2\text{MeSiSiMe}_2\text{H}$  (55:45) was formed. These results suggest that a variety of metal complexes may be used as the catalytic species in the chemistry described, including preferential isomer formation, and we are actively pursuing this concept.

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